

| L Number | Hits | Search Text   | DB  | Time stamp       |
|----------|------|---|---|------------------|
| 1        | 9010 | ((Chemical adj mechanical adj polish\$3 ) or CMP or planariz\$5) and (slurry or composition)  | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/13 14:28 |
| 8        | 3477 | ( ((Chemical adj mechanical adj polish\$3 ) or CMP or planariz\$5) and (slurry or composition)) and (((Chemical adj mechanical adj polish\$3 ) or CMP or planariz\$5) same (metal\$1 or tungsten))                                  | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/13 14:30 |
| 15       | 27   | ( ( ((Chemical adj mechanical adj polish\$3 ) or CMP or planariz\$5) and (slurry or composition)) and (((Chemical adj mechanical adj polish\$3 ) or CMP or planariz\$5) same (metal\$1 or tungsten))) and (ammonium adj nitrate\$1) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/13 14:31 |